



Precision of Micro Hall Effect Measurements in Scribe Line Test Pads of B-doped SiGe

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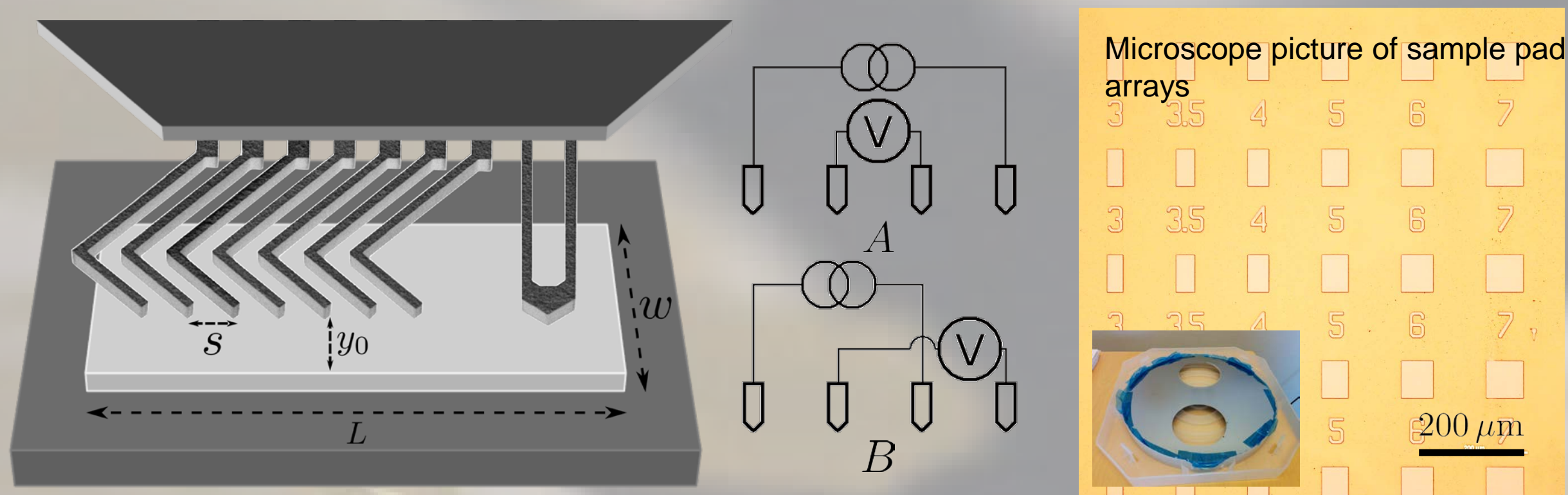
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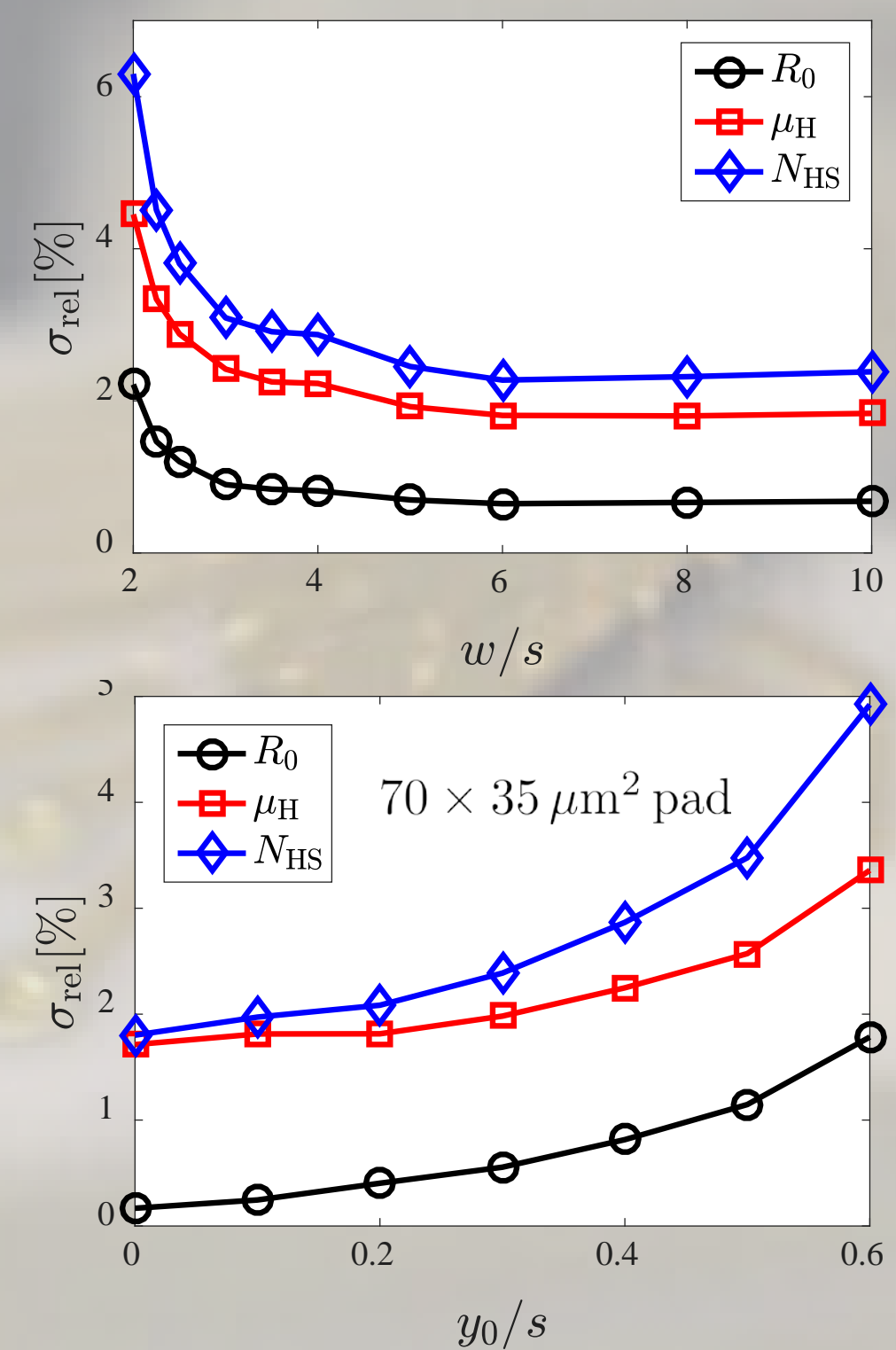
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Measurement Technique

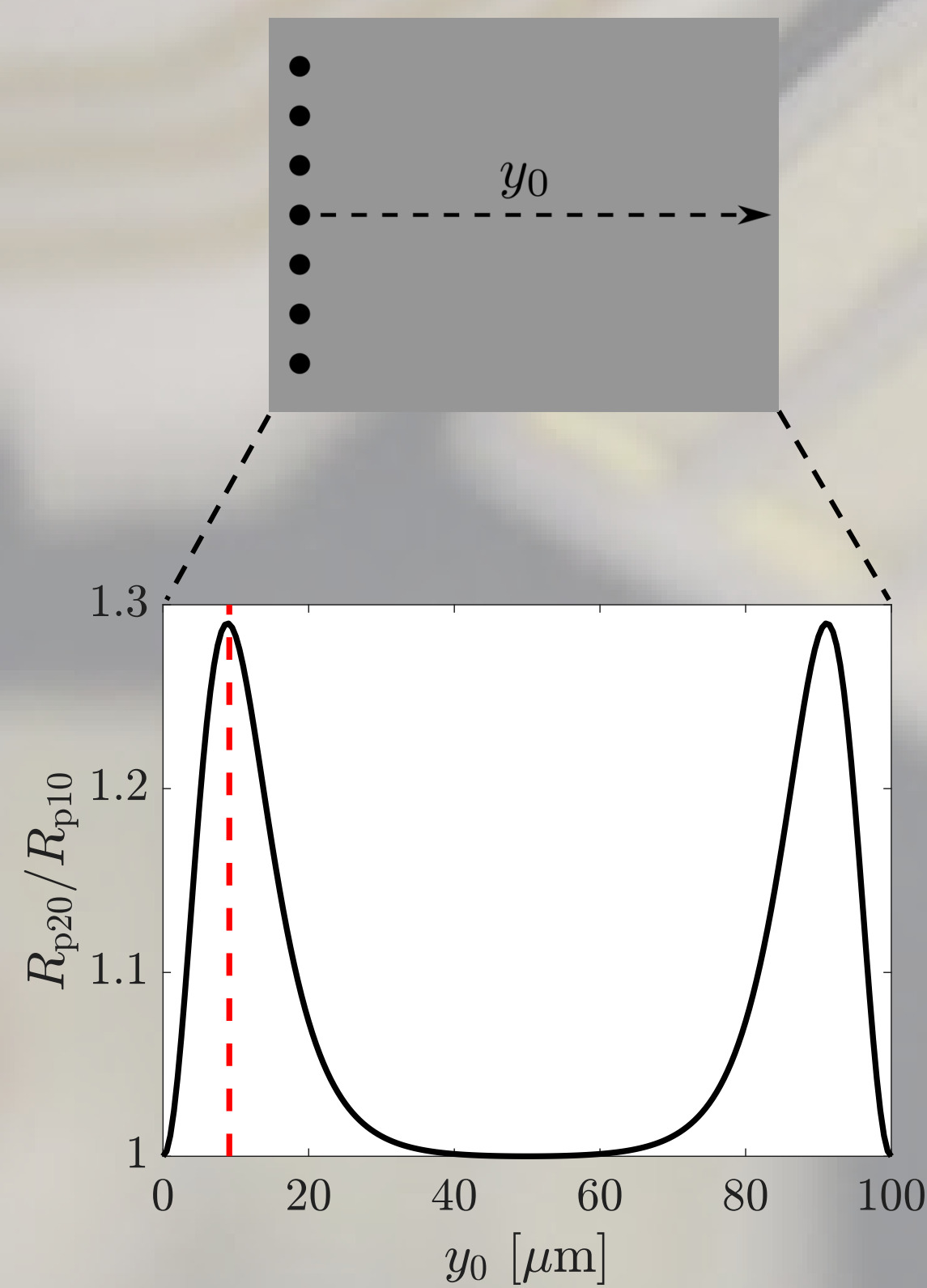


Monte Carlo Simulation of Measurement Errors

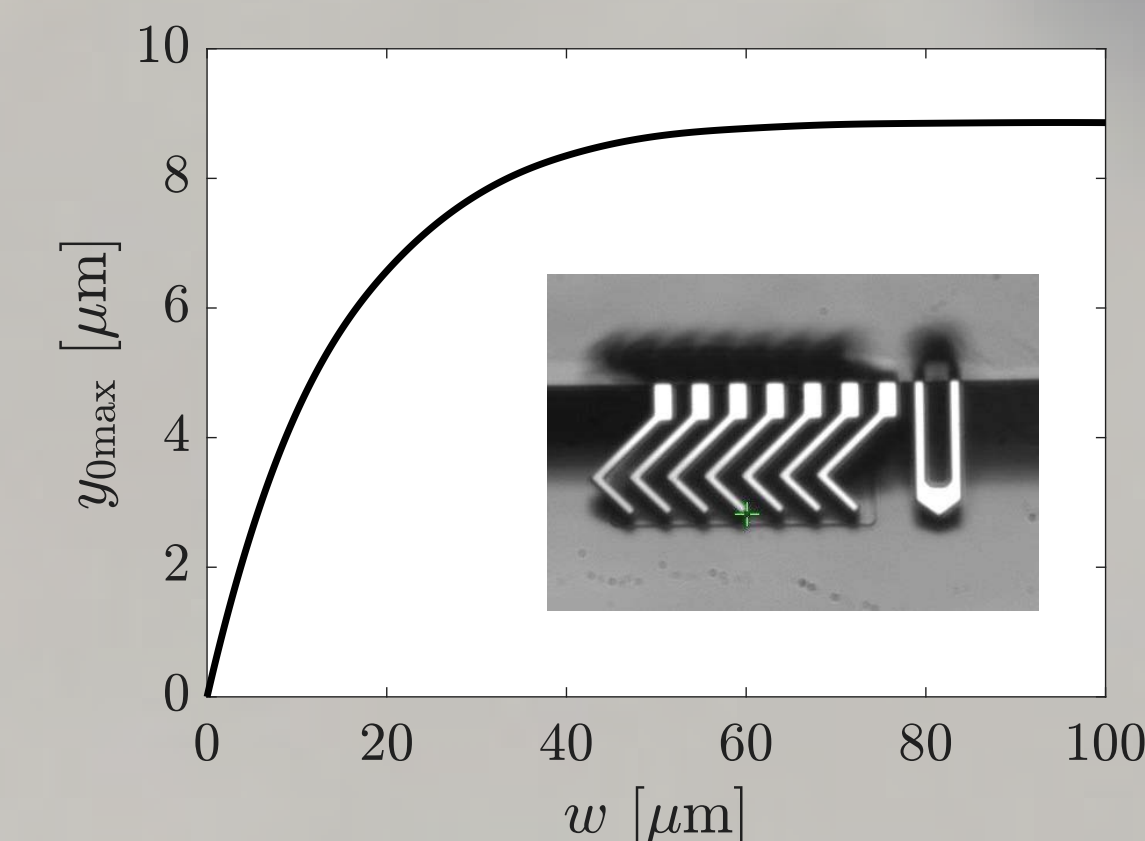


Distance to the Edge

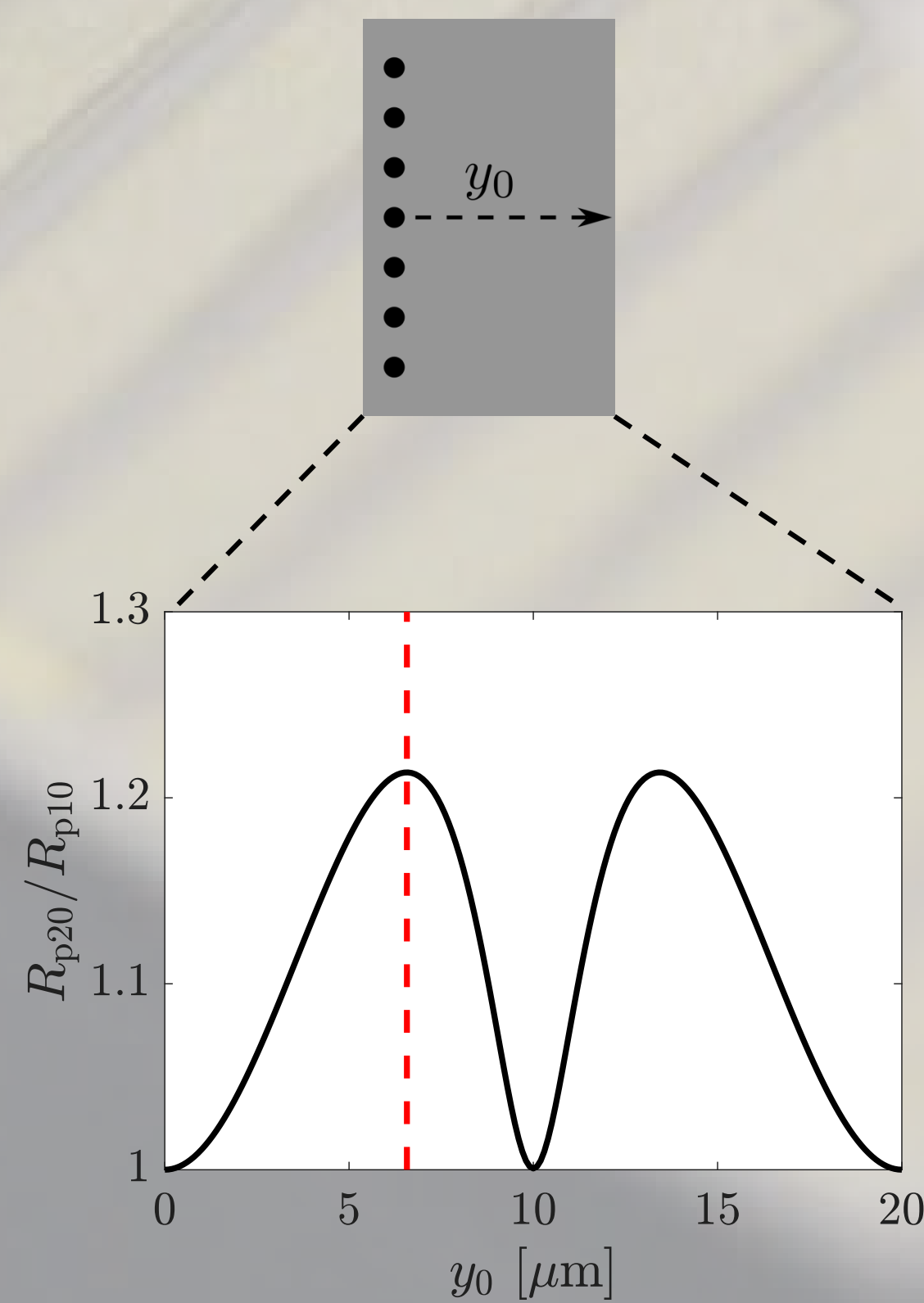
Determining probe distance to the edge, y_0 , on a big pad (100 μm)



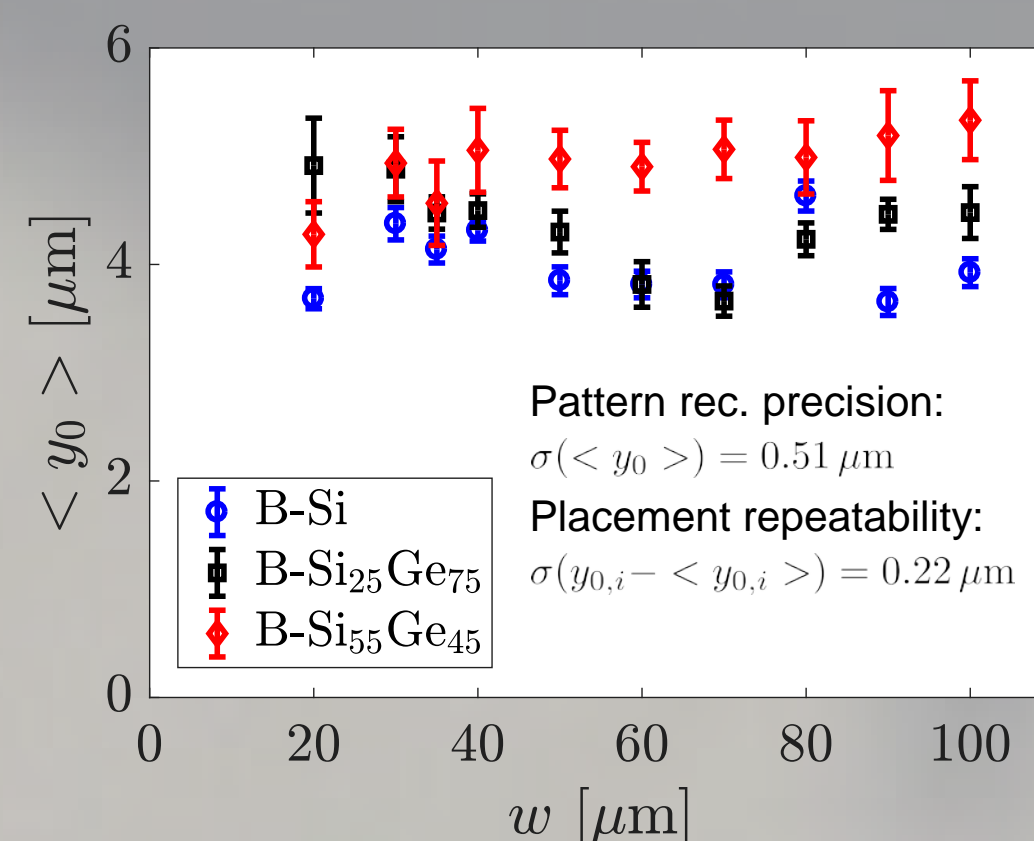
Maximum probe landing distance from the edge, $y_{0\text{max}}$, vs. pad size, w, to ensure correct y_0 calculation



Determining probe distance to the edge, y_0 , on a small pad (20 μm)



Standard deviation on mean distance to the edge, $\langle y_0 \rangle$, vs. pad size, w, for different samples



Experimental Measurement Errors on B-doped SiGe Pads

